CryoVac

株式会社 クライオバック

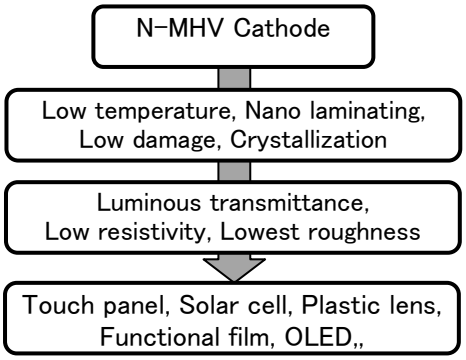
N-MHV Cathode

New Product!! V form Sputter Cathode

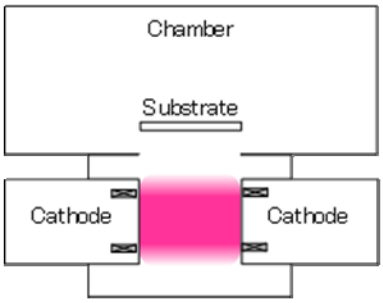
N－MHV Cathode （New Magnetic Hollow-cathode V-formation）
To provide a method for forming a functional thin film on low-melting point materials such as Plastic film and sheet,

Newly developed "N-MHV Cathode" has excellent properties by unique design like, '
- **V-form facing targets**
- **Multipolar Magnetic**

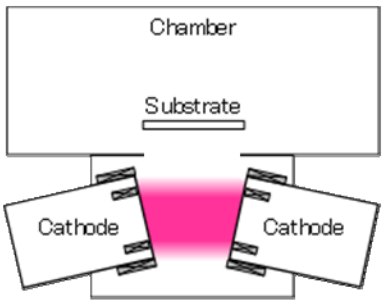
And, N-MHV Cathode enables to get,
- **Forming with lower voltage**
- **Higher density plasma**
- **Low temperature process**
- **Lower damage**
- **Film forming speed improvement**

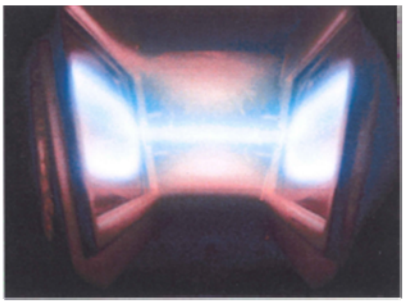


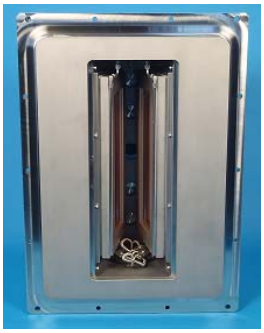
Standard facing Cathode



N-MHV Cathode







Data by N-MHV cathode

ITO on PET film:
- Resistivity(ρ) : 2.9 X 10^{-4} Ω cm
- Luminous transmittance (T) : 88.2% (λ : 550nm)

⇒ For TCO layer

Cu layer on Polyimide film:
- Forming speed : 1.8 μ m/min (≦100℃)
- Peel strength : 10N/cm

⇒ For multilayer FPC (Flexible printed circuits)

＊ This N-MHV catode is technically licensed from, "Ogawa souzou gijyutsu kenkyusho". (Patent)

CryoVac
12-14,2-Chome,Chibune,Nishiyodogawa-ku,
Osaka,555-0013 Japan
TEL : +81-6-6475-5266 FAX : +81-6-6475-7330
Cryovac Corporation
E-mail : info@cryovac.jp